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APPLICATION NO.		FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/062,141		01/31/2002	Richard W. Sexton	SDP271PA	2522
1333	7590	11/01/2005		EXAMINER	
BETH RE	AD		CHEA, THORL		
PATENT L			ART UNIT	PAPER NUMBER	
343 STATE		K COMPANY T	1752		
ROCHEST	ER, NY	14650-2201	DATE MAILED: 11/01/2005		

Please find below and/or attached an Office communication concerning this application or proceeding.

		1		/	
		Application No.	Applicant(s)		
		10/062,141	SEXTON, RICHAF	SEXTON, RICHARD W.	
	Office Action Summary	Examiner	Art Unit	-	
		Thorl Chea	1752		
Period f	The MAILING DATE of this communication apport in the mail of th	pears on the cover shee	t with the correspondence ad	dress	
THE - External control	MORTENED STATUTORY PERIOD FOR REPL MAILING DATE OF THIS COMMUNICATION. ensions of time may be available under the provisions of 37 CFR 1.1 r SIX (6) MONTHS from the mailing date of this communication. Per period for reply specified above is less than thirty (30) days, a reploperiod for reply is specified above, the maximum statutory period ure to reply within the set or extended period for reply will, by statute reply received by the Office later than three months after the mailing the patent term adjustment. See 37 CFR 1.704(b).	136(a). In no event, however, ma ly within the statutory minimum of will apply and will expire SIX (6) it e, cause the application to becom	y a reply be timely filed  thirty (30) days will be considered timely MONTHS from the mailing date of this co e ABANDONED (35 U.S.C. § 133).		
Status					
1) 又	Responsive to communication(s) filed on 15 A	ugust 2005.			
·		s action is non-final.			
′=	· · · · · · · · · · · · · · · · · · ·		natters, prosecution as to the	merits is	
,	closed in accordance with the practice under	Ex parte Quayle, 1935 (	C.D. 11, 453 O.G. 213.		
Disposit	ion of Claims				
4)⊠	Claim(s) 13 and 22-29 is/are pending in the ap	oplication			
٠,١	4a) Of the above claim(s) is/are withdra		•		
5)□	Claim(s) is/are allowed.				
′	Claim(s) <u>13 and 22-29</u> is/are rejected.				
7)	Claim(s) is/are objected to.				
•	Claim(s) are subject to restriction and/o	or election requirement.			
Applicat	ion Papers		•		
9)	The specification is objected to by the Examine	er.			
'=	The drawing(s) filed on is/are: a) ☐ acc		to by the Examiner.		
,—	Applicant may not request that any objection to the		•		
	Replacement drawing sheet(s) including the correct			R 1.121(d).	
11)	The oath or declaration is objected to by the Ex	xaminer. Note the attac	hed Office Action or form PT	O-152.	
Priority	under 35 U.S.C. § 119				
•	Acknowledgment is made of a claim for foreign ☐ All b) ☐ Some * c) ☐ None of:	priority under 35 U.S.C	C. § 119(a)-(d) or (f).		
	1. Certified copies of the priority document				
	2. Certified copies of the priority document				
	3. Copies of the certified copies of the prior		een received in this National	Stage	
	application from the International Burea	, , , , , , , , , , , , , , , , , , , ,			
* (	See the attached detailed Office action for a list	of the certified copies i	not received.		
Attachmer	nt(s)				

U.S. Patent and Trademark Office PTOL-326 (Rev. 1-04)

1) Notice of References Cited (PTO-892)

Paper No(s)/Mail Date \_\_\_

2) Notice of Draftsperson's Patent Drawing Review (PTO-948)
3) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08)

4) Interview Summary (PTO-413)

6) Other: \_\_\_\_.

Paper No(s)/Mail Date. \_\_\_\_\_.

5) Notice of Informal Patent Application (PTO-152)

#### **DETAILED ACTION**

1. The disclosure is objected to because of the following informalities: see page 5, lines 21-35 wherein Fig. 2H and Fig. 2I are not shown in the drawing. It should be changed to Fig. 3A and Fig.3B respectively.

Appropriate correction is required.

## Claim Rejections - 35 USC § 112

2. The following is a quotation of the first paragraph of 35 U.S.C. 112:

The specification shall contain a written description of the invention, and of the manner and process of making and using it, in such full, clear, concise, and exact terms as to enable any person skilled in the art to which it pertains, or with which it is most nearly connected, to make and use the same and shall set forth the best mode contemplated by the inventor of carrying out his invention.

3. Claims 13, 22-29 are rejected under 35 U.S.C. 112, first paragraph, as failing to comply with the written description requirement. The claim(s) contains subject matter which was not described in the specification in such a way as to reasonably convey to one skilled in the relevant art that the inventor(s), at the time the application was filed, had possession of the claimed invention. The specification as originally filed fails to provide support for the language "a conductive metal layer applied to the sacrificial controlled-release layer, the conductive metal layer having a surface contactable with the three dimensional electroformed structure, the conductive metal layer having an adhesive bond associated with the three dimensional electroformed structure, the adhesive bond between the conductive metal layer and the three dimensional electroformed structure being stronger than the adhesive bond between the sacrificial controlled-release layer and the substrate base, wherein the three dimensional electroformed structure is removable from substrate base before being removable from the conductive metal layer".

The paragraph [0018] of the application publication (US 2003/0143492A1) discloses, "[0018] When both layers are plated, the photoresist layer 18 is removed to separate the orifice plate from the mandrel base. For removal and recycling, the orifice plate 14 of FIG. 1 can be soaked in acetone until the parting resist layer 18 is dissolved, resulting in the structure shown in FIG. 2H. Alternatively, the multilayer orifice plate 14 may be carefully peeled, fracturing the brittle parting resist layer 18. Resist can then be chemically stripped from the orifice plate 14 and the base substrate 16. The thin copper layer 20 which has remained on the separated orifice plate is then removed with a selective etchant, leaving the completed orifice plate structure shown in FIG. 2I. The selective etchant would remove copper but not damage the nickel during the short immersion period required to etch away the copper. The orifice plate is then ready to be assembled into an ink jet printhead". Therefore, the languages presented in the claims are not supported by the paragraph pointed out by the applicants. Therefore, they raise the issue of new matter.

### Claim Rejections - 35 USC § 103

- 4. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
  - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 5. Claims 13, 22-29 are rejected under 35 U.S.C. 103(a) as being unpatentable over Lam et al (US Patent No. 4,773,971) in view of Roos (US Patent No. 4,268,610).

Lam et al discloses a mandrel of claim 8 in column 6 of Lam et al which having a glass substrate, an adhesion sheet layer and a stainless steel sheet layer. The mandrel is used in the

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process in producing ink jet printhead (column 2, lines 36-63; Sheet 5 of 10, Fig. 4C and Sheet 10 of 10, Fig. 8C). See also in column 3, lines 15-30 wherein the chrome layer is disclosed. Roos discloses a photoresist compositons with improved adhesion properties for used in making printing circuit board, lithographic plates, relief image plates or cylinders and for other applications in the photographic art. The invention deals with photoresist formulations with improved adhesion properties in both solvent and aqueous developable film so as to resist chemical attack and other kinds of degradation during etching, plating and other processing in any known manner. The resist formulation has may advantage such as capable of easy removal from metal surface during development, does not interfere with the plating cycle or leaching into plating bath; and enable the metal surface to be cleaned with water or weak acid or basis solution without the need for persulfate etch. See abstract and column column 2, lines 39-54. It would have obvious to the worker of ordinary skill in the art at the time the invention was made would have selected an adhesion layer having property equivalent to that of adhesion layer taught in Lam such as photoresist formulation taught in Roos with an expectation of achieving a layer that has improved adhesion properties in both solvent and aqueous developable film so as to resist chemical attack and other kinds of degradation during etching, and plating and, and thereby provide a mandrel as claimed. The property such as "brittle" is inherent to the layer forming by the dried resist taught in Roo.

## Response to Arguments

6. Applicant's arguments filed August 15, 2005 have been fully considered but they are not persuasive for the new ground of rejection. The claimed invention is directed to a madrel for use in a fabrication of a three dimentional electroform structure. The composition of the

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mandrel is a substrate base having a sacrificial-releasing layer and a condutive metal layer applied. The limitation that directed to three dimensional electroformed structures is related to the final product obtained by the using the mandrel. Therefore, the limitation such as ""a conductive metal layer applied to the sacrificial controlled-release layer, the conductive metal layer having a surface contactable with the three dimensional electroformed structure, the conductive metal layer having an adhesive bond associated with the three dimensional electroformed structure, the adhesive bond between the conductive metal layer and the three dimensional electroformed structure being stronger than the adhesive bond between the sacrificial controlled-release layer and the substrate base, wherein the three dimensional electroformed structure is removable from substrate base before being removable from the conductive metal layer" fails to limit the structure of the mandrel which is an intermediate product for the production of an three dimentional electroformed such as ink jet print head.

The applicants argue that the Roo's ('610) reference discloses a photoresist improve adhesion properties (abstract). However, delamination actually occurs between the metal layer and the electroformed structure, and not between the metal layer and the substrate.

The argument is not persuasive. The applicants is referred to Fig.1 wherein the madrel having substrate (16), releasing layer 18, and a metal layer (20), and Fig. 2G to Fig.3A wherein the nickel layer which is built up on the thin copper layer (20) by electroformed. The copper layer and the electroformed nickel was peeled off from the substrate (16), and the then electroformed nickel (24) is separated from the thin copper layer. The copper layer (20) which remains on the separate orifice plate is then removed by etchant but not damage the nickel during the short immersion period required to etched away the copper (page 2, 0018). There is no adhesive bond

between the electroformed structure and conductive metal layer is found. Moreover, the electrostructure is not considered as part of the madrel, and it fails to further limit the structure of the madrel presented in the claimed and in the specification disclosure. Accordingly, the mandrel having structure as claimed would have been found prima facie obvious to the worker of ordinary skill in the art in view of the combination of the applied prior art such as presented above.

### Conclusion

7. Applicant's amendment necessitated the new ground(s) of rejection presented in this Office action. Accordingly, **THIS ACTION IS MADE FINAL**. See MPEP § 706.07(a). Applicant is reminded of the extension of time policy as set forth in 37 CFR 1.136(a).

A shortened statutory period for reply to this final action is set to expire THREE MONTHS from the mailing date of this action. In the event a first reply is filed within TWO MONTHS of the mailing date of this final action and the advisory action is not mailed until after the end of the THREE-MONTH shortened statutory period, then the shortened statutory period will expire on the date the advisory action is mailed, and any extension fee pursuant to 37 CFR 1.136(a) will be calculated from the mailing date of the advisory action. In no event, however, will the statutory period for reply expire later than SIX MONTHS from the date of this final action.

8. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Thorl Chea whose telephone number is (571) 272-1328. The examiner can normally be reached on 9 AM-5:30 PM.

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If attempts to reach the examiner by telephone are unsuccessful, the examiner's

supervisor, Cynthia H. Kelly can be reached on (571)272-1526. The fax phone number for the

organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent

Application Information Retrieval (PAIR) system. Status information for published applications

may be obtained from either Private PAIR or Public PAIR. Status information for unpublished

applications is available through Private PAIR only. For more information about the PAIR

system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR

system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Tchea the October 21, 2005

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